

IN THE CLAIMS:

Please amend claims 1-4, 7 and 8 as follows:

Claim1 (currently amended): An electron microscope for observing ~~faults and/or foreign objects~~ of a surface or inside of a semiconductor wafer or a mask for exposing a semiconductor pattern for faults and/or foreign objects, comprising

a function of loading measurement data of coordinates or sizes of said faults and/or foreign objects which were observed ~~obtained by observing said semiconductor or said mask~~ with another wafer or mask inspecting apparatus, moving a field of view of the electron microscope to an area where said fault and/or foreign object exists ~~based on said measurement data~~, and simultaneously displaying said coordinates of said faults and/or objects which were obtained by observing said semiconductor wafer or said mask with said another wafer or mask inspecting apparatus, said field of view of said electron microscope moved according to the coordinates of said faults and/or objects, and which were obtained by another wafer or mask inspecting apparatus a vicinity (24) thereof on a display and an area indicating said field of view of the electron microscope within its vicinity area,

a function of a pointing device having a switch pointer ~~which moves said field of view (26) of the electron microscope to a position which is pointed to by a pointer on said display and an area indicating said field of view of said electron microscope to a position on said vicinity area which is pointed to by the pointer,~~ and

a function of changing said field of view ~~displayed on said display according to said moving of said field of view pointed to by said switch of said electron microscope by moving said area indicating said field of view of said electron microscope on said vicinity area.~~

Claim 2 (currently amended): An electron microscope in accordance with Claim 1, wherein the pointer switch of said pointing device has a function to magnify or shrink the field of view of the electron microscope and its vicinity area at any rate.

Claim 3 (currently amended): An electron microscope in accordance with Claim 1, further comprising a function which magnifies or shrinks said field of view of the electron microscope and its vicinity area as the field of view moves on a screen displaying said field of view of the electron microscope and its vicinity area.

Claim 4 (currently amended): An electron microscope in accordance with Claim 1, further comprising a function which moves and displays the center coordinates of the field of view and its vicinity area as said field of view moves.

Claim 5 (original): An electron microscope in accordance with Claim 1, further comprising a function which displays shapes of faults on the screen displaying said field of view and a function which changes the display on the screen as the observing conditions of the electron microscope change.

Claim 6 (original): An electron microscope in accordance with Claim 1, further comprising a function which displays coordinates of faults or objects obtained by said another wafer or mask inspecting apparatus and distances of the field of view of the electron microscope, a function which stores said distance values, and a function which relatively moves the field of view of the electron microscope by said stored distances.

Claim 7 (currently amended): An electron microscope in accordance with Claim 1, further comprising a function which displays an observed area and a non-observed area separately on the screen displaying said field of view and its vicinity area, and a function which changes said display as the observing conditions of the electron microscope change.

Claim 8 (currently amended): An electron microscope for observing ~~faults and/or foreign objects~~ of a surface or inside of a semiconductor wafer or a mask for exposing a semiconductor pattern for faults and/or foreign objects, comprising:

a memory device for storing coordinate information or sizes of said faults ~~and/or foreign~~ objects which ~~are~~ were obtained ~~by observing said semiconductor wafer or said mask with~~ another wafer or mask inspecting apparatus,

a control computer for controlling so as to move a field of view of said electron microscope to an area where a fault of foreign object exists based on said coordinate information, and

a display for simultaneously displaying said coordinates of said faults ~~and/or~~ objects which were obtained by observing said semiconductor wafer or said mask with said another wafer or mask inspecting apparatus, said field of view of said electron microscope moved according to the coordinates of said faults or objects which were obtained by another wafer or mask inspecting apparatus and an area indicating said field of view of the electron microscope within its vicinity area, and its vicinity based on said coordinate information stored in said memory device,

a pointing device ~~for pointing a part of said vicinity on said display~~ which moves said area indicating said field of view of said electron microscope to a position on said vicinity area which is pointed by the pointing device, wherein

said control computer controls said electron microscope so as to move said field of view of said electron microscope to said position on said vicinity area which is to a coordinate of said part pointed to by said pointing device, and

said display displays said semiconductor wafer or a mask observed in said field of view at ~~said coordinate of said part~~ to said position on said vicinity area which is pointed to by said pointing device.